

IN THE CLAIMS:

Please amend the claims as follows:

1. (Canceled)
2. (Currently Amended) A pedestal for supporting a substrate in a plasma etching chamber, comprising:
a body, the body being configured to receive an RF power; and
a substrate support base along an upper surface of the body, the substrate support base having an outer edge, and an intermediate substrate support ridge for receiving and supporting the substrate, wherein at least a portion of the substrate support base outside of the intermediate substrate support ridge is fabricated from a dielectric material having a lower dielectric constant than a remaining portion of the substrate support base, and wherein the portion of the substrate support base within the substrate support ridge is fabricated from a metallic material.
3. (Original) The pedestal of claim 2, wherein the portion of the substrate support base fabricated from a dielectric material is formed by placing a layer of dielectric material along a top surface of the substrate support base outside of the substrate support ridge in order to form a dielectric ring.
4. (Original) The pedestal of claim 3, wherein the substrate support ridge is fabricated from a metallic material.
5. (Original) The pedestal of claim 3, wherein the dielectric material is fabricated from materials selected from the group consisting of a polymeric material, a ceramic material, and combinations thereof.
6. (Original) The pedestal of claim 2, wherein the portion of the substrate support base fabricated from a dielectric material defines substantially the entire thickness of the substrate support base outside of the substrate support ridge.
7. (Original) The pedestal of claim 6, wherein the substrate support ridge is fabricated from a metallic material.

8. (Original) The pedestal of claim 6, wherein the dielectric material is fabricated from materials selected from the group consisting of a polymeric material, a ceramic material, and combinations thereof.

9-10. (Canceled)

11. (Currently Amended) A pedestal for supporting a reticle in a plasma etching chamber, comprising:

a body, the body being configured to receive an RF power; and

a reticle support base along an upper surface of the body, the reticle support base having an outer edge and an intermediate reticle support ridge for receiving and supporting the reticle, wherein at least a portion of the reticle support base outside of the intermediate reticle support ridge is fabricated from a dielectric material having a lower dielectric constant than a remaining portion of the substrate support base and wherein a portion of the reticle support base within the reticle support ridge is fabricated from a metallic material.

12-15. (Canceled)

16. (Currently Amended) A plasma etching chamber having a pedestal therein for supporting a reticle, comprising:

a chamber body defining a base wall, a side wall and a dome;

a gate along the side wall for permitting a reticle to be moved into the plasma etching chamber; and

a reticle support member for supporting a reticle within the plasma etching chamber during processing, the reticle support member comprising:

a body, the body being configured to receive an RF power; and

a reticle support base along an upper surface of the body, the reticle support base having an outer edge and an intermediate reticle support ridge for receiving and supporting the reticle, wherein at least a portion of the reticle support base outside of the intermediate reticle support ridge is fabricated from a dielectric material having a lower dielectric constant than a remaining portion of the substrate support base, a portion of the reticle support base within the reticle

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support ridge is fabricated from a metallic material, and the reticle support ridge is fabricated from a metallic material.

17-19. (Canceled)

20. (Previously Presented) The pedestal of claim 11, wherein the reticle support ridge is fabricated from a metallic material.